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**PATENT NUMBER and
ISSUE DATE**
U.S. UTILITY Patent Application

APPL NUM 10/034745 1647382	FILING DATE 01/14/2002	CLASS 5643	SUBCLASS 1	GAU 1703	EXAMINER
**APPLICANTS: Sharan Sujit; Sandhu Gurtej; Smith Paul; Chang Mei;					
**CONTINUING DATA VERIFIED: THIS APPLICATION IS A DIV OF 09/026,042 02/19/1998					
** FOREIGN APPLICATIONS VERIFIED:					
PG-PUB DO NOT PUBLISH <input type="checkbox"/>		RESCIND <input type="checkbox"/>			
Foreign priority claimed <input type="checkbox"/> yes <input type="checkbox"/> no 35 USC 119 conditions met <input type="checkbox"/> yes <input type="checkbox"/> no Verified and Acknowledged Examiners's initials				ATTORNEY DOCKET NO M122-1902	
TITLE : RF powered plasma enhanced chemical vapor deposition reactor and methods of effecting plasma enhanced chemical vapor deposition					
<small>U.S. DEPT. OF COMM./PAT. & TM.-PTO.-16L (Rev. 12-94)</small>					

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NOTICE OF ALLOWANCE MAILED		CLAIMS ALLOWED	
		Assistant Examiner	Total Claims Print Claim for O.G.
ISSUE FEE		DRAWING	
Amount Due	Date Paid	Primary Examiner	Sheets Drwg. Figs. Drwg. Print Fig.
<input type="checkbox"/> TERMINAL DISCLAIMER		PREPARED FOR ISSUE	Application Examiner
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